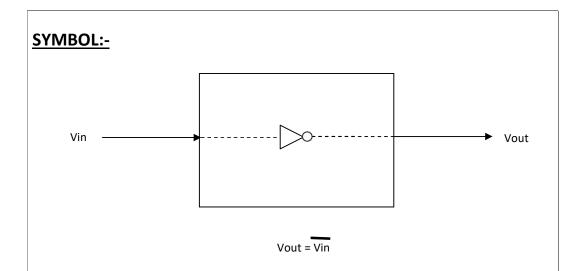
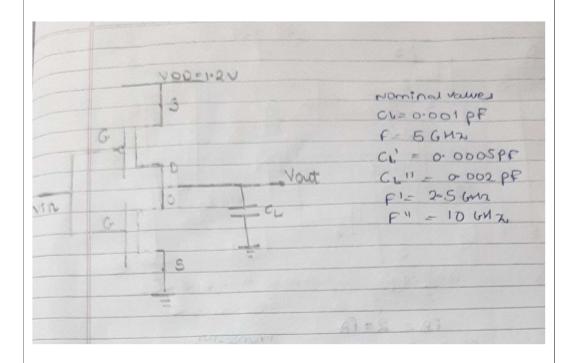
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Class	:	
Batch	:	
Roll. No	:	
ABC ID	:	
Assignment No.	:	B.1.a
Assignment Name	:	CMOS INVERTER & Dynamic Power Dissipation Analyses
Date Of Performance	:	



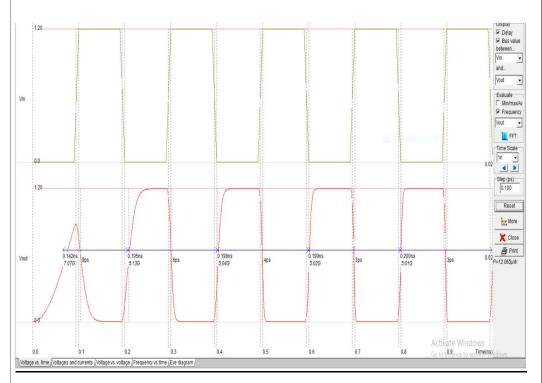


Truth Table:-Vin Vout Strong-1 (1.2 V) 0 Strong-0 (0 V) 1

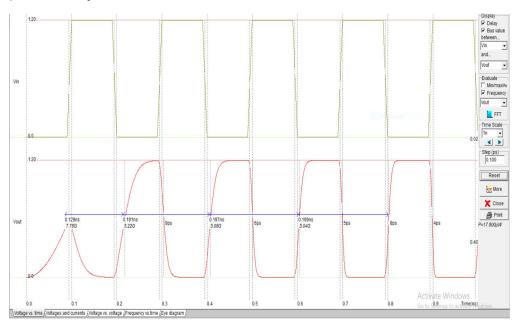
<u>Layout for 90 nm Foundry</u> : ($V_{dd} = 1.2 V$) Vdd+ CMOS 90nm, 6 Metal Copper - strained SiGe - LowK (1.20V,2.50V)

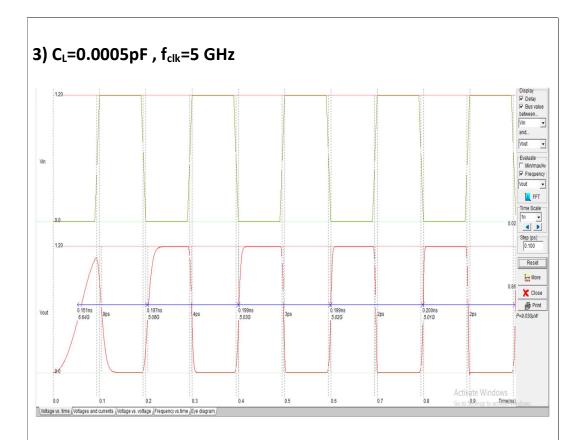
Waveforms:

1) C_L =0.001pF , f_{clk} =5 GHz

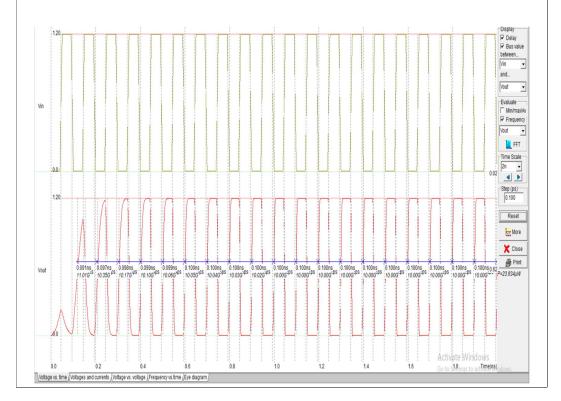


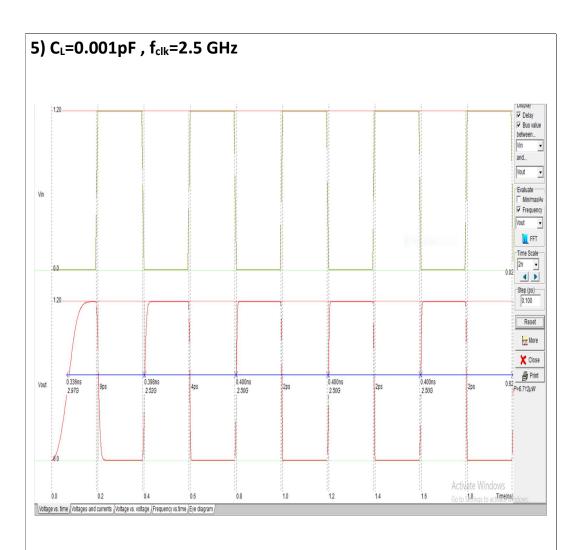
2) C_L=0.002pF , f_{clk}=5 GHz





4) C_L =0.001pF , f_{clk} =10 GHz





DYNAMIC POWER DISSIPATION ANALYSES

(I) Effect of change in C_L :

SR.NO.	C _L (pF)	P _{dyn} (μW)
1)	0.001	12.488
2)	0.002	18.627
3)	0.0005	9.485

(II) Effect of change in f_{clk} :

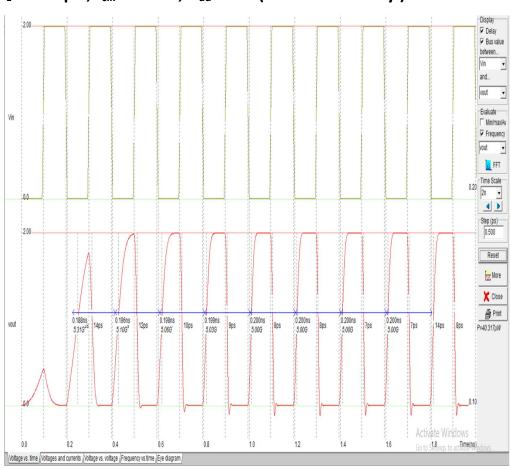
SR.NO.	f _{clk} (GHz)	P _{dyn} (μW)
1)	5	12.488
2)	2.5	6.712
3)	10	23.834

Layout for 180nm foundry : ($V_{dd} = 2 V$) Vdd+ Vdd+ vout 0.001pF

Set CLOCK parameters as : Time low = Time High = 0.090 nS Rise Time = Fall Time = 0.01 nS

Waveforms:-

$C_L {=}\, 0.001 pF$, $f_{clk} {=} \ 5 \ GHz$, $V_{dd} {=} \ 2 \ V$ ($180 \ nm$ Foundry)



DYNAMIC POWER DISSIPATION ANALYSES

V _{dd} (V)	P _{dyn} (μW)
1.2 (90 nm)	12.488
2 (180 nm)	40.317

Conclusions:-

- 1) Drawn the LAYOUT for CMOS Inverter using 90 nm & 180 nm Foundry.
- 2) Simulated LAYOUT to observe w/f's & verified functionality.
- 3) Being a **Pure-CMOS System** (PMOS // NMOS & CMOS INVERTER) , it gives both **S-1** & **S-0** as O/P.
- 4) Appreciated the validity of the mathematical model

$$P_{dynamic} = C_L * (Vdd)^2 * f_{clk}$$

- 5) Found a reduction in P_{dynamic} by using a better Foundry i.e., **90 nm** instead of **180** nm
- 6) Learnt that the presence of spikes in O / P waveform at Switching instants indicate the inability of the MOSFETs to switch at GHz frequencies.